	Application No.	Applicant(s)	
Notice of Allowability	10/535,372	GRUTZMACHER ET AL.	
	Examiner	Art Unit	
	Chukwuma O. Nwaonicha	1621	
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication IGHTS. This application is subject to	plication. If not included will be mailed in due could	rse. THIS
1. This communication is responsive to <u>18 December 2006</u> .			
2. X The allowed claim(s) is/are 1-11.	·		-
 3. Acknowledgment is made of a claim for foreign priority unappriority and a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). 	been received. been received in Application No		from the
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the require	ements
 A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give 			CE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		•
(a) including changes required by the Notice of Draftspers	on's Patent Drawing Review (PTO-	948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the C	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the	.84(c)) should be written on the drawin he header according to 37 CFR 1.121(ngs in the front (not the bac d).	k) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 			the
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Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	5. ☐ Notice of Informal P	atent Application	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary	(PTO-413),	
3. Information Disclosure Statements (PTO/SB/08),	Paper No./Mail Dat 7.		
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material		ent of Reasons for Allowar	ice
	SUPERVIS	URMAN K. PAGE ORY PAYENT EXAMINER OLOGY CENTER 1600	·

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DETAILED ACTION

Current Status

- 1. This action is responsive to Applicants' communication of 18 December 2006.
- 2. Receipt and entry of Applicants' amendment is acknowledged.
- 3. Claims 1-11 are in active consideration in the application.
- 4. The 102 rejections have been withdrawn because applicants have amended the claims to overcome the rejection.

Allowed Claims

Claims 1-11 are allowable over the prior art of record.

Reason For Allowance

The following is an examiner's statement of reasons for allowance: Applicants claim a process for preparing a cycloorganylphosphsphane of the general formula (**R 1P**)_n with activated zinc in an organic solvent or with sodium in a non-polar organic solvent in the presence of tetramethylethylenediamine, and a di(alkali metal/alkaline earth metal) oligophosphanediide of formula 1, 2 or 3;

wherein all the variables are as defined in the claims. The process for preparing a cycloorganylphosphsphane of the general formula $(R_1P)_n$ and a di(alkali metal/alkaline

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earth metal) oligophosphanediide of formula 1, 2 or 3 were neither found to be obvious nor anticipated by the prior art of record.

The closest prior art is Goerlich et al., {Tris-1-Adamantylcyclotriphosphine and Tetrakis-1-Adamantylcyclotetraphosphine: Two Peradamantylated Examples from the Cyclopolyphosphine Series (RP)n, Zeitschrift Fuer Anorganische und Allgemeine Chemie, 1994, 620 (1), 173-176}. Goerlich et al. teach a process for the preparation of a cycloorganylphosphsphane as shown below by reacting a halocompound and sodium under reflux condition.

formula 2

Applicants process for making cycloorganylphosphsphane differs from the process of Goerlich et al. in that applicants claim a process that employs tetramethylethylenediamine while Goerlich et al. process is conducted without this particular compound. These differences are not readily apparent and would not have been suggested to one of ordinary skill.

All claims (1-11) are allowed.

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to 5:00pm.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

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accompany the issue fee. Such submissions should be clearly labeled "Comments on

Statement of Reasons for Allowance".

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chukwuma O. Nwaonicha whose telephone number is 571-272-2908. The examiner can normally be reached on Monday thru Friday, 8:30am

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Thurman k. Page can be reached on 571-272-0602. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Chukwuma O. Nwaonicha, Ph.D. Patent Examiner

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Thurman Page,

Supervisory Patent Examiner,

Technology Center 1600